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Atty. Dkt. No. 039153-0351 (F0879)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Babcock

Title: Growth Of Photoresist Layer In
Photolithographic Process

Appl. No.: 10/097,637

Filing Date: 3/14/02

Examiner: Unknown

Art Unit: Unknown

CERTIFICATE OF MAILING I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as First Class Mail in an envelope addressed to: Commissioner for Patents, Washington, D.C. 20231, on the date below. <u>Chris Escoville</u> (Printed Name) <u>Chris Escoville</u> (Signature) <u>4/10/02</u> (Date of Deposit)

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
Washington, D.C. 20231

Sir:

Pursuant to 37 C.F.R. §§ 1.97-98 and in accordance with the duty of disclosure under 37 C.F.R. §1.56, Applicant submits herewith the references listed on the attached Form PTO-1449 to the Examiner such that they may be considered and made of record in the above-identified application. A copy of each reference is enclosed.

Applicant also brings to the Examiner's attention the following related applications:

U.S. Appl. No. 09/769,197, entitled "Dual Damascene Process Using Self-Assembled Monolayer", filed January 24, 2001, by Krivokapic, et al. (Atty. Dkt No. 39153/321).

U.S. Appl. No. 09/774,939, entitled "Dual Gate Fabrication Process Using Self-Assembled Molecular Layer", filed January 31, 2001, by Krivokapic (Atty. Dkt. No. 39153/316).

U.S. Appl. No. 10/097,819, entitled "Reducing Feature Dimension Using Self-Assembled Monolayer", filed March 14, 2002, by Babcock (Atty. Dkt. No. 39153/342).

U.S. Appl. No. 09/772,597, entitled "Dual Damascene Process Using Self-Assembled Monolayer and Spacers", filed January 30, 2001, by Krivokapic (Atty. Dkt. No. 39153/353).

Copies of the applications are enclosed pursuant to 37 C.F.R. §1.98(a)(2)(iii).

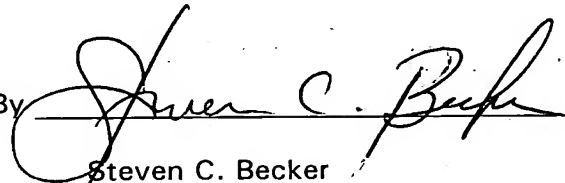
Respectfully submitted,

Date

4/10/02

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Form PTO-1449 (MODIFIED)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. 39153/351 (F0879)	SERIAL NO. 10/097,637
INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)		APPLICANT Babcock	
		FILING DATE 3/14/2002	GROUP ART UNIT Unknown

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB- CLASS	FILING DATE IF APPROPRIATE
		6,087,231	7/11/2000	Xiang et al.	438	287	
		5,727,977	3/17/1998	Maracas et al.	445	24	
		5,079,600	1/7/1992	Schnur et al.	357	4	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

		Joanna Aizenberg, Andrew J. Black and George M. Whitesides, Controlling local disorder in self-assembled monolayers by patterning the topography of their metallic supports, Nature, August 27, 1998, pp. 868-871
		Self-Assembled Monolayers, printed from Internet address: http://www.ifm.liu.se/applphys/molfil...ject/monolayerstructure/sam/sams.html on October 9, 2000, 5 pages
		Self-assembled mono-multilayers, printed from Internet address: http://www.inapg.inra.fr/ens_rech/siab/asteq/elba/salayers.htm on November 14, 2000, 3 pages
		Thin Semiconductor Layers Prepared from Langmuir-Blodgett Precursor, printed from Internet address: http://www.foresight.org/Conferences/MNT6/Papers/Erokhin/ on November 14, 2000, 9 pages
		Monolayer Basics, printed from Internet address: http://www.langmuir-blodgett.com/basics/faq1.htm on November 14, 2000, 6 pages
		Monolayer History, printed from Internet address: http://www.langmuir-blodgett.com/basics/faq2.htm on November 14, 2000, 3 pages
		Langmuir Blodgett Assembly, printed from Internet address: http://mmpwww.ph.qmw.ac.uk/lbassem.html on November 14, 2000, 2 pages
		Lu et al., Ultrathin resist films patterning using a synchrotron radiation lithography system, September 7, 1996, pp. 103-105
		Huang et al., Photopatterning of Self-Assembled Alkanethiolate Monolayers on Gold: A Simple Monolayer Photoresist Utilizing Aqueous Chemistry, January 7, 1994, pp. 626-628
		Aoki et al., Molecular Patterning using Two-Dimensional Polymer Langmuir-Blodgett Films, Advanced Materials 1997, 9, No. 4, pp. 361-364
		Oh et al., Fabrication and Photodegradation Behavior of Photosensitive Polyimide LB Film, Mol. Cryst. and Liq. Cryst. 2001, Vol. 370, pp. 169-172
		Iwamoto et al., Fine Patterns of Positive-Working Resists Using a Polyimide Langmuir-Blodgett Film System, Japanese Journal of Applied Physics, Vol. 30, No. 2A, February, 1991, pp. L218-L221

EXAMINER

DATE CONSIDERED

* EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include any copy of this form with next communication to applicant.

Form PTO-1449
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PATENT AND TRADEMARK OFFICE

ATTY. DOCKET NO.

039153-0351 (F0879)

SERIAL NO.

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APPLICANT

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(Use several sheets if necessary)

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB- CLASS	FILING DATE IF APPROPRIATE
		6,262,456	7/14/01	Yu, et al.	257	371	
		6,225,658	5/1/01	Watanabe	257	296	
		6,174,775	1/16/01	Liaw	438	283	
		6,187,657	2/13/01	Xiang	438	596	
		6,238,982	5/29/01	Krivokapic, et al.	438	275	

FOREIGN PATENT DOCUMENTS

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB- CLASS	TRANSLATION	
							YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

		U.S. Publication No. US 2001/000629 A1, filed May 3, 2001, by Tsukamoto, entitled "Semiconductor Device and Process of Producing the Same".

EXAMINER

DATE CONSIDERED

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